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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/773,744	02/06/2004	Kurt D. Sieber	83996RLO 8618		
7590 07/28/2005			EXAMINER		
Pamela R. Crocker			DANG, TRUNG Q		
Patent Legal St	aff				
Eastman Kodak	Company	ART UNIT	PAPER NUMBER		
343 State Street	t	2823			
Rochester, NY 14650-2201			DATE MAILED: 07/28/2005		

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application	on No.	Applicant(s)					
Office Action Summary		10/773,74		SIEBER ET AL.	(ar				
		Examine		Art Unit	(4)				
		Trung Dai		2823	_				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply									
A SHOTHE I - Exter after - If the - If NO - Failu Any r	ORTENED STATUTORY PERIOD FOR IN MAILING DATE OF THIS COMMUNICAT asions of time may be available under the provisions of 37 sIX (6) MONTHS from the mailing date of this communicat period for reply specified above is less than thirty (30) day period for reply is specified above, the maximum statutory the to reply within the set or extended period for reply will, by reply received by the Office later than three months after the patent term adjustment. See 37 CFR 1.704(b).	TION. CFR 1.136(a). In no evition. s, a reply within the static period will apply and with static period with sta	ent, however, may a reply be tim utory minimum of thirty (30) day ill expire SIX (6) MONTHS from lication to become ABANDONE	nely filed s will be considered timely the mailing date of this co D (35 U.S.C. § 133).					
Status									
2a)⊠	Responsive to communication(s) filed on <u>18 May 2005</u> . This action is FINAL . 2b) This action is non-final. Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.								
Dispositi	on of Claims								
5)⊠ 6)⊠ 7)□	Claim(s) 4,11 and 13-18 is/are pending in 4a) Of the above claim(s) is/are wind Claim(s) 4,11 and 13 is/are allowed. Claim(s) 15-18 is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction	ithdrawn from co	nsideration.						
Applicati	on Papers								
10)⊠	The specification is objected to by the Extended The drawing(s) filed on 18 May 2005 is/and Applicant may not request that any objection Replacement drawing sheet(s) including the Cather oath or declaration is objected to by	re: a)⊠ accepte to the drawing(s) t correction is requir	ne held in abeyance. See an ed if the drawing(s) is obj	e 37 CFR 1.85(a). lected to. See 37 CF					
Priority u	ander 35 U.S.C. § 119								
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No. 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 									
Attachmen	t(s)								
1) Notic 2) Notic 3) Infor	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-9 nation Disclosure Statement(s) (PTO-1449 or PTO/ r No(s)/Mail Date		4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:)-152)				

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 2. Claims 15-18 are rejected under 35 U.S.C. 102(e) as being anticipated by Hasegawa et al. (US 2004/0031926) in view of Seki (US 2003/0137242), all of record.

With reference to Figs. 5 - 6, Hasegawa teaches a method of making an electronic device in which a conductive electrode 4 of indium-tin-oxide (ITO) has been formed over a substrate, comprising:

producing a fluorocarbon plasma in a plasma apparatus to form a fluorocarbon layer CF_x 35 over the conductive electrode by selecting a mixture of gases including a fluorine containing gas CF_4 which will cause a thicker deposition of the fluorocarbon layer CF_x 35 over the electrode than regions adjacent to the electrode.

See paras. [0086], [0087], [0091]. Note that, as shown in Fig. 6, the CFx layer 35 is formed only over electrode 4 but not over adjacent regions comprising layer 33, hence the claimed limitation regarding a thicker deposition of the fluorocarbon layer

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over the electrode than regions adjacent to the electrode is met by the reference.

Hasegawa differs from the claims in not disclosing an oxidizing plasma process to modify the properties of the electrode as recited in step a) of claim 15.

Seki teaches a plasma treatment process in which a surface of an ITO electrode is first treated with O_2 plasma to modify the properties of the electrode and then the modified electrode is treated with fluorocarbon-based plasma including CF_4 plasma (paras. [0180], [0182], [0184], [0186], [0187]).

It would have been obvious to one of ordinary skill in the art to modify Hasegawa's process by modifying the properties of the electrode 4 using the O_2 plasma treatment prior to the fluorocarbon-based plasma treatment as suggested by Seki because the O_2 plasma treatment would facilitate fluorination therefore enhancing the adherence of the fluorocarbon layer CF_x 35 to the electrode 4.

For the claimed limitation regarding the use of appropriately positioned plasma producing electrodes, see Fig. 7 in Seki.

For claim 16, the mixture of gases (CF_4 and O_2) disclosed in para. [0087] of the primary reference does not contain hydrogen, a noble gas, and a hydrogen containing gas.

For claim 17, while Hasagawa teaches in para. [0106] that the above fluorocarbon plasma treatment can be performed by exposing electrode 4 to radicals containing fluorine that is generated in a plasma formed from a gas mixture of CF₄, CHF₃ and Ar, the claim calls for a gas mixture contain CF₄, CHF₃ and helium (He).

However, substitution of He for Ar in the gas mixture of Hasegawa would have been obvious to one of ordinary skill in the art because He and Ar are both belong to a group of rare gases (He, Ne, Ar, Kr, Xe, Rn) that exhibit similar chemical properties, hence one skilled in the art would reasonable expect that using He in place of Ar in the gas mixture of Hasegawa would yield similar effect.

Claim Rejections - 35 USC § 112

3. The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claim 17 is rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

Claim 17 is indefinite in that claim 17 depends on claim 16 which recites a mixture of gases that is **not** containing a noble gas and a hydrogen containing gas, yet claim 17 recites the gas mixture contain helium and CHF₃ which are a noble gas and a hydrogen containing gas, respectively

Allowable Subject Matter

- 4. Claims 4, 11, 13, 14 are allowed over prior art of record.
- 5. The following is an examiner's statement of reasons for allowance:

Claim 13 and its dependent claims are allowed over prior art of record because the prior art does not teach or suggest the claimed subject matter, which includes the

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claimed feature regarding using a shaped electrodes to produce <u>a spatially modulated</u> <u>fluorocarbon plasma</u> in the chamber so as to form a fluorocarbon layer in selected areas of the substrate electrode structure.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

6. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

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7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Trung Dang whose telephone number is 571-272-1857. The examiner can normally be reached on Mon-Friday 9:30am-6:00pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on 571-272-1855. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For

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more information about the PAIR system, see http://pair-direct.uspto.gov.

Trung Dang Primary Examiner Art Unit 2823

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